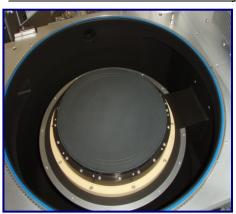
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CHAMBER LINER CHAMBER

VACUUM CHAMBER PM TECHNIQUE LAM 2300 EXELAN FLEX OXIDE ETCH CHAMBER

OBJECTIVE:

TO EFFECTIVELY PM THE LAM 2300 EXELAN FLEX OXIDE ETCH CHAMBER IN A TIMELY MANNER, WHILE IMPROVING TOOL RECOVERY AND PARTICLE PERFORMANCE

Vacuum Chamber: LAM 2300 EXELAN FLEX OXIDE ETCH

Vacuum Chamber Process Residue: PROCESS INDUCED RESIDUE

Vacuum Chamber Components: CHAMBER, CHAMBER LINERS AND ASSOCIATED

PARTS

Old Procedure: 2+ hours using silicon carbide scrubbing pads with ethanol

(or equivalent final wipe solvent) 100+ wipes

Tool recovery: 6 to 8 hours conditioning wafers

New Procedure: 1 hour using 800D ScrubPAD, DI water & ethanol (or

equivalent final wipe solvent)

Tool recovery: < 4 Hours conditioning wafers

Vacuum Chamber Products: LAM2300 EXELAN OXIDE ETCH PM KIT PM Kit P/N: HT4500-LAM23-OX1

- (1) <u>HT4754</u> UltraSOLV[®] Sponge
- (2) HT4580D-10-1 800 Grit Diamond ScrubPAD
- (4) <u>HT1511FC</u>-5 MiraSWABS[®] (20pc)
- (1) <u>HT5790S</u>-25 MiraWIPES[®] (25pc)



View "How to" instructional videos on http://www.foamtecintlwcc.com/flash/

Step 1: Using proper procedures and safety guidelines, shutdown and prepare LAM 2300 Exelan Flex Chamber for wet clean

Step 2: Properly stage a container of DI water next to the chamber and place a Foamtec International <a href="https://example.com/https://example.

Fig 1: ScrubPAD and UltraSOLV® Sponge in container of DI water

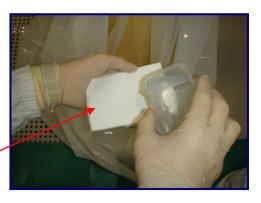


NOTE: MAY SUBSTITUE A SMALL AMOUNT OF DI WATER TO MOISTEN UltraSOLV® SPONGE AND ScrubPAD AS NECESSARY (See Fig 2 & 3)



Fig 2: UltraSOLV[®] Sponge, ScrubPAD and small amount of DI water

Fig 3: Dampening UltraSOLV® Sponge with DI water



Step 3: Use the **lightly dampened** UltraSOLV® Sponge and wipe Oxide ETCH Chamber liners (See Fig 4)

Fig 4: Dampened UltraSOLV® Sponge wiping chamber liners

Step 4: Use a **lightly dampened** 800 Grit Diamond ScrubPAD and scrub off deposition from Oxide ETCH Chamber liner. It is important to keep area a little moist with DI water (See Fig 5 & 6)

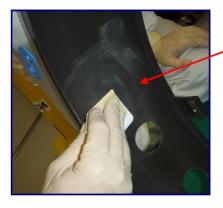


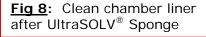
Fig 5 & 6: Lightly dampened 800 Grit Diamond ScrubPAD scrubbing chamber liner; keep slightly moist with DI water

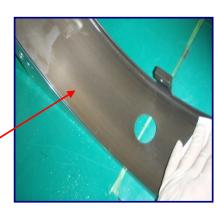


Step 5: Before oxide deposition has a chance to dry back onto the chamber liner, use lightly dampened UltraSOLV® Sponge and wipe deposition from chamber liner (See Fig 7 & 8)

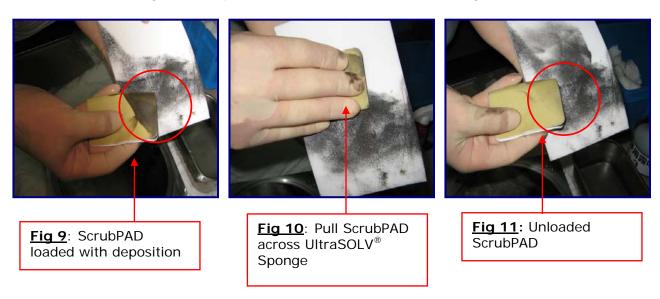


<u>Fig 7</u>: Lightly dampened UltraSOLV[®] Sponge preparing to wipe chamber liner





Step 6: As Diamond ScrubPAD appears to load up with deposition, pull ScrubPAD across damp UltraSOLV® Sponge. This will help keep ScrubPAD effectively removing oxide deposition from chamber liner (See Fig 9, 10 & 11)



Step 7: Continue to rinse UltraSOLV® Sponge in container of DI water as necessary to keep UltraSOLV® Sponge slightly moist and free of deposition (See Fig 12 & 13)

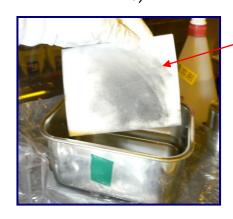


Fig 12: Loaded-up UltraSOLV[®] Sponge

Fig 13: UltraSOLV® Sponge AFTER rinse



Step 8: Continue to repeat this SCRUB – WIPE – RINSE procedure outlined in steps 4 thru 7 for the remainder of the LAM 2300 Oxide ETCH parts (See Fig 14, 15

& 16)





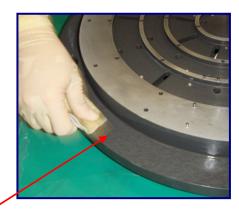
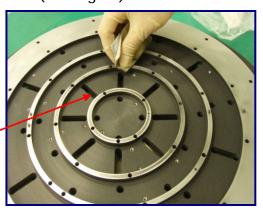


Fig 14, 15 & 16: Continuing SCRUB – WIPE – RINSE procedure on remaining Oxide ETCH Chamber parts

Step 9: Using same technique described above, take 800 Grit Diamond ScrubPAD and gently remove dark build-up on heater coils (See Fig 17)





IMPORTANT NOTE

IN ORDER TO HELP WITH AN EFFECTIVE TOOL RECOVERY, FOAMTEC INTERNATIONAL WIPE DOWN PROCEDURE MUST BE FOLLOWED WITH ALL <u>HT5790S</u> MiraWIPES® AND <u>HT1511FC</u> MiraSWABS®. THE MICRO-FIBER CHARACTERISTICS OF THESE PRODUCTS HELP REMOVE MORE DEPOSITION FROM THE PARTS THAN ANY OTHER STANDARD FAB WIPER

NOTE:

Figure below shows how much more deposition the Foamtec International MiraWIPE® can remove from a critical surface compared to the standard fab wiper, making the MiraWIPE® FINAL WIPE PROCEDURE the most **CRITICAL STEP** of the PM procedure (See Fig 18a & 18b)

Fig 18a: Current fab wiper after completely wiping LAM 2300



Fig 18b: Particles picked up using HT5790S MiraWIPES® after completely wiping with current fab wiper

MiraWIPES® are the <u>KEY STEP</u> for <u>DEFECT</u>
REDUCTION and IMPROVED TOOL RECOVERY

Step 10: After scrubbing heater coils use the <u>HT1511FC</u> Miraswab. dampened with alcohol and clear out all openings on heater plate (See Fig 19 & 20)

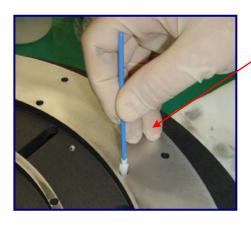
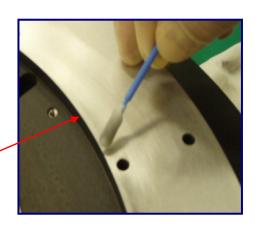


Fig 19: HT1511FC
MiraSWAB® clearing out openings on heater plate

Fig 20: Additional deposition MiraSWAB® was able to remove from openings



Step 11: While using the HT1511FC MiraSWABS® to clear out all the openings within the heater coils, also use the HT5790S MiraWIPES® dampened with alcohol and proceed to wipe the entire heater plate, concentrating on the tight corners throughout the heater plate (See Fig 21 & 22)

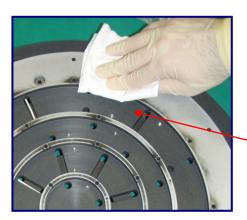
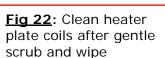
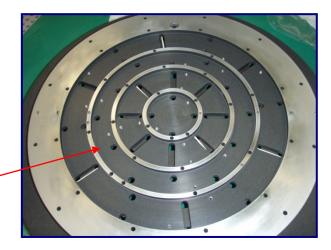


Fig 21: Wiping heater plate with <a href="https://example.com/http





Step 12: Following the same procedure with the <u>HT1511FC</u> MiraSWABS® and <u>HT5790S</u> MiraWIPES® with alcohol, perform an entire wipe of the remaining Oxide ETCH parts prior to placing back into the Oxide ETCH Chamber (See Fig 23)

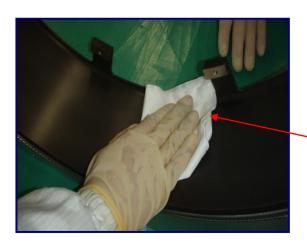
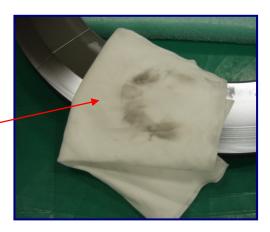


Fig 23: HT5790S MiraWIPE® performing final wipe on all chamber parts

NOTE: THE FOLLOWING SHOWS HOW MUCH MORE DEPOSITION THE MIRAWIPE® WAS ABLE TO REMOVE FROM A SMALL SECTION OF THE SILICONE RING AFTER A COMPLETE WIPED DOWN WITH THE STANDARD FAB WIPER (See Fig 24 & 25)



Fig 24 & 25: THE IMPORTANCE OF USING THE HT5790S



CHAMBER CLEAN:

Step 13: Take the additional 800 Grit Diamond ScrubPAD and using the same technique described above proceed to perform a chamber scrub on the LAM 2300 Exelan Flex Oxide Chamber

NOTE: Ensure to concentrate on the heavy deposition areas that are not covered by the chamber liners, such as the sides of the e-chuck (See Fig 26)

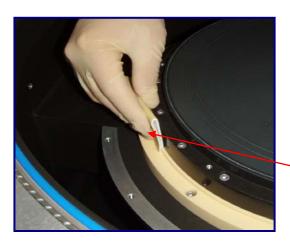


Fig 26: 800 Grit Diamond ScrubPAD gently scrubbing edge of e-chuck

Step 14: When entire chamber scrub is complete, use the same technique described above and use remaining <u>HT1511FC</u> MiraSWABS[®] and <u>HT5790S</u> MiraWIPES[®] with alcohol and perform a complete chamber wipe down (See Fig 27 & 28)



<u>Fig 27</u>: Applying alcohol to HT5790S MiraWIPE®

Fig 28: Performing final wipe of LAM Oxide Chamber



TOOL RECOVERY:

Step 15: Follow proper tool recovery guidelines as outlined by LAM Research Corporation